

L Number	Hits	Search Text	DB	Time stamp
1	62271	(etch\$3 clean\$3) and (wafer substrate) and (bath container tank)	USPAT; US-PGPUB	2003/07/05 15:37
2	3382	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))	USPAT; US-PGPUB	2003/07/05 15:38
4	2842	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)	USPAT; US-PGPUB	2003/07/05 15:38
5	830	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution) ) and ("HF" (hydrogn near fluoride) (hydro near3 fluoric near3 acid))	USPAT; US-PGPUB	2003/07/05 15:38
6	7119	(etch\$3 clean\$3) and (wafer substrate) and (bath container tank)	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
7	2798	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
8	1722	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
9	50	((etch\$3 clean\$3) and (wafer substrate) and (bath container tank) ) and ((etch\$3 clean\$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution) ) and ("HF" (hydrogn near fluoride) (hydro near3 fluoric near3 acid))	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:39